

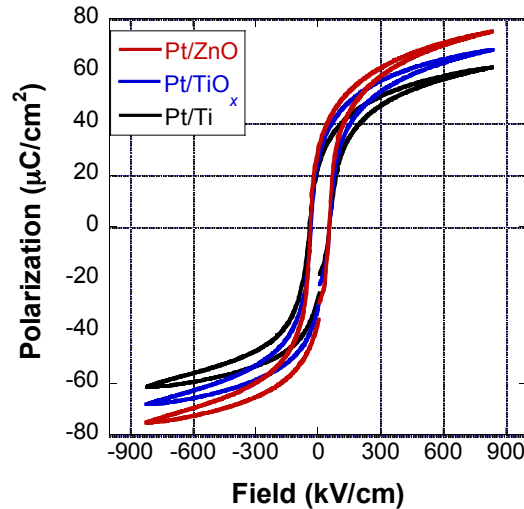
Solution Chemistry, Substrate, and Processing Effects on the Chemical Heterogeneity in PZT Films

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Collaborators

Sandia National Labs

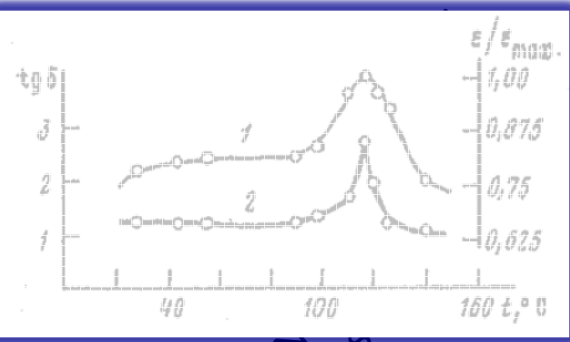
Microscopy

- Paul Kotula
- Bryan Gauntt
- Ping Lu
- Bonnie McKenzie
- Amy Allen
- Michael Rye
- Chris T. Shelton

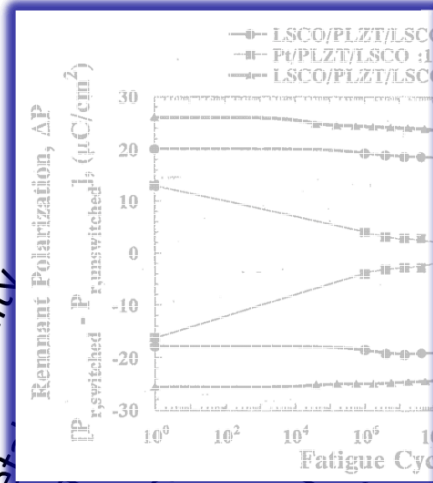
Solution/Film Preparation

- Dara V. Gough
- Geoff Brennecke
- Erik Spoerke
- Mia Blea-Kirby
- Kelsey Meyer
- Harlan Brown-Shaklee

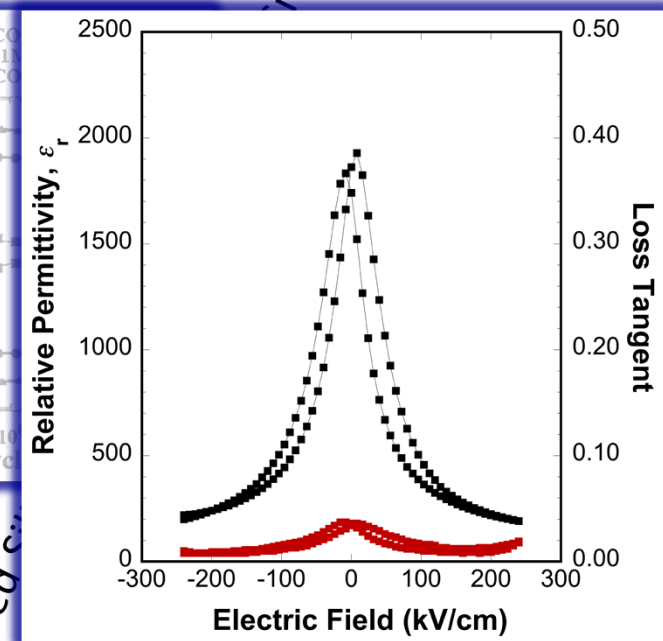
A brief history of ferroelectric thin film substrates*



Platinum /
Pratt & Fires
others



Platinized Silicon: Pt/SiO₂/Si
Virtually Entire Community
Non-Noble Metals
Sayer, Newnham



Platinized Silicon
Virtually Entire
Conductive Oxide
Kington and Ramo

Platinized Silicon
Dimos, Base, Kington

Base, Clem

??

Despite these substrate advances platinized silicon is by far the most utilized in R&D and piezo-MEMS settings

Lessons Learned (and forgotten?)

Fox, *et al.* 1994

Kim, *et al.* 2000

Tani and Payne 1992

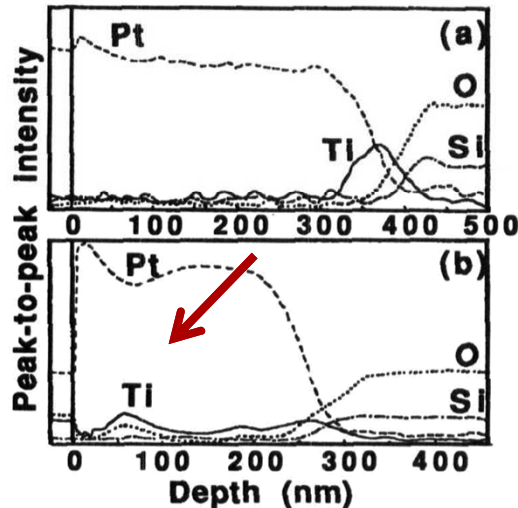
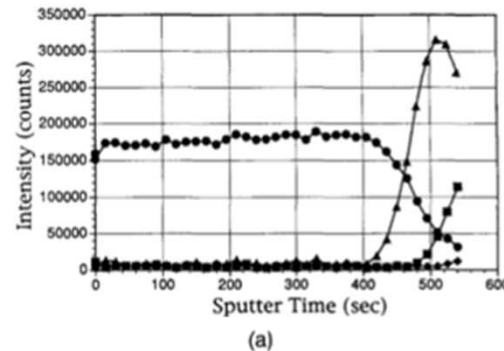
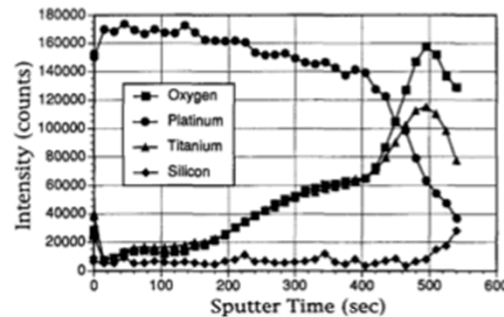


Fig.2 AES of A substrates (a) before and (b) after annealing at 650 °C for 30 min.



(a)



(b)

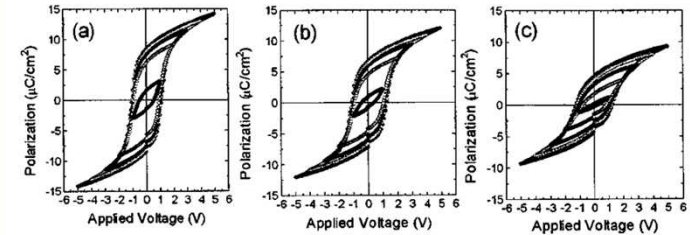
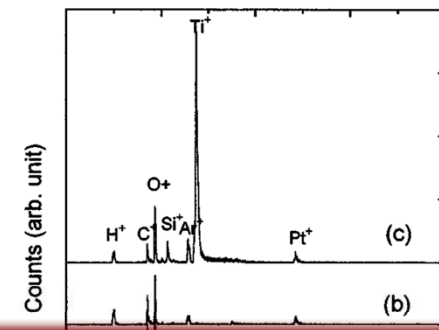
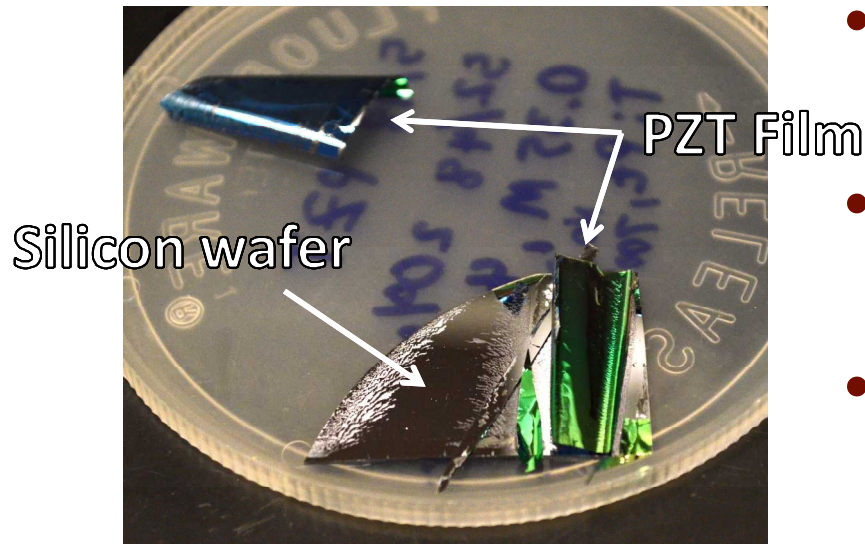
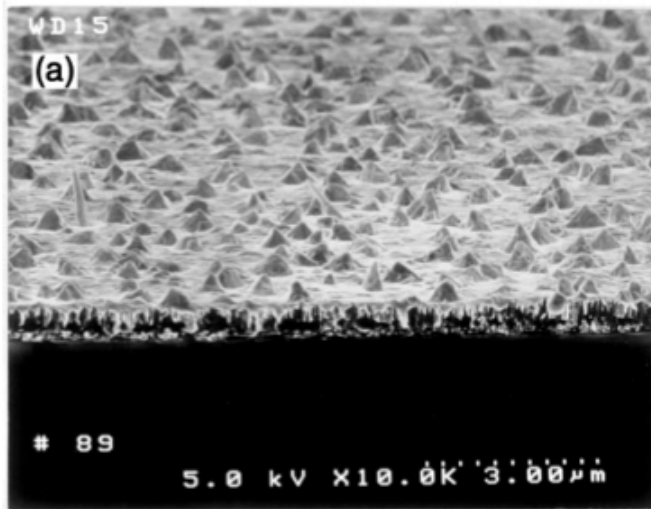


FIG. 2. $P-V$ hysteresis loops of SBT thin films (a) on Pt/ZrO₂/SiO₂/Si, (b) Pt/TiO₂/SiO₂/Si, and (c) Pt/Ti/SiO₂/Si substrates.



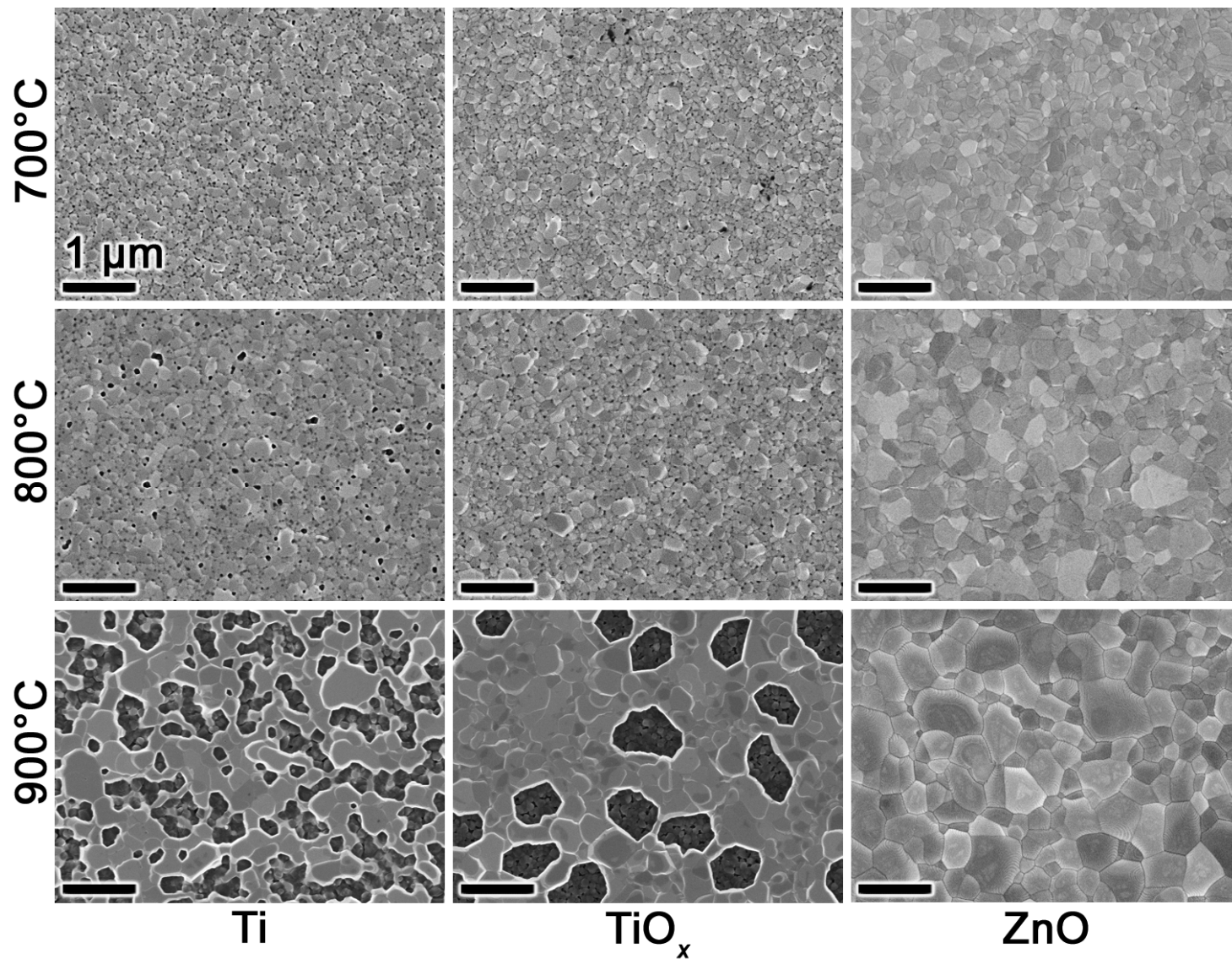
- Electrode/adhesion layer stacks cannot be considered as inert bystanders!
- Titanium-based adhesion layers are known to diffuse through platinum

Pt/Ti remains state of the art in platinized silicon:

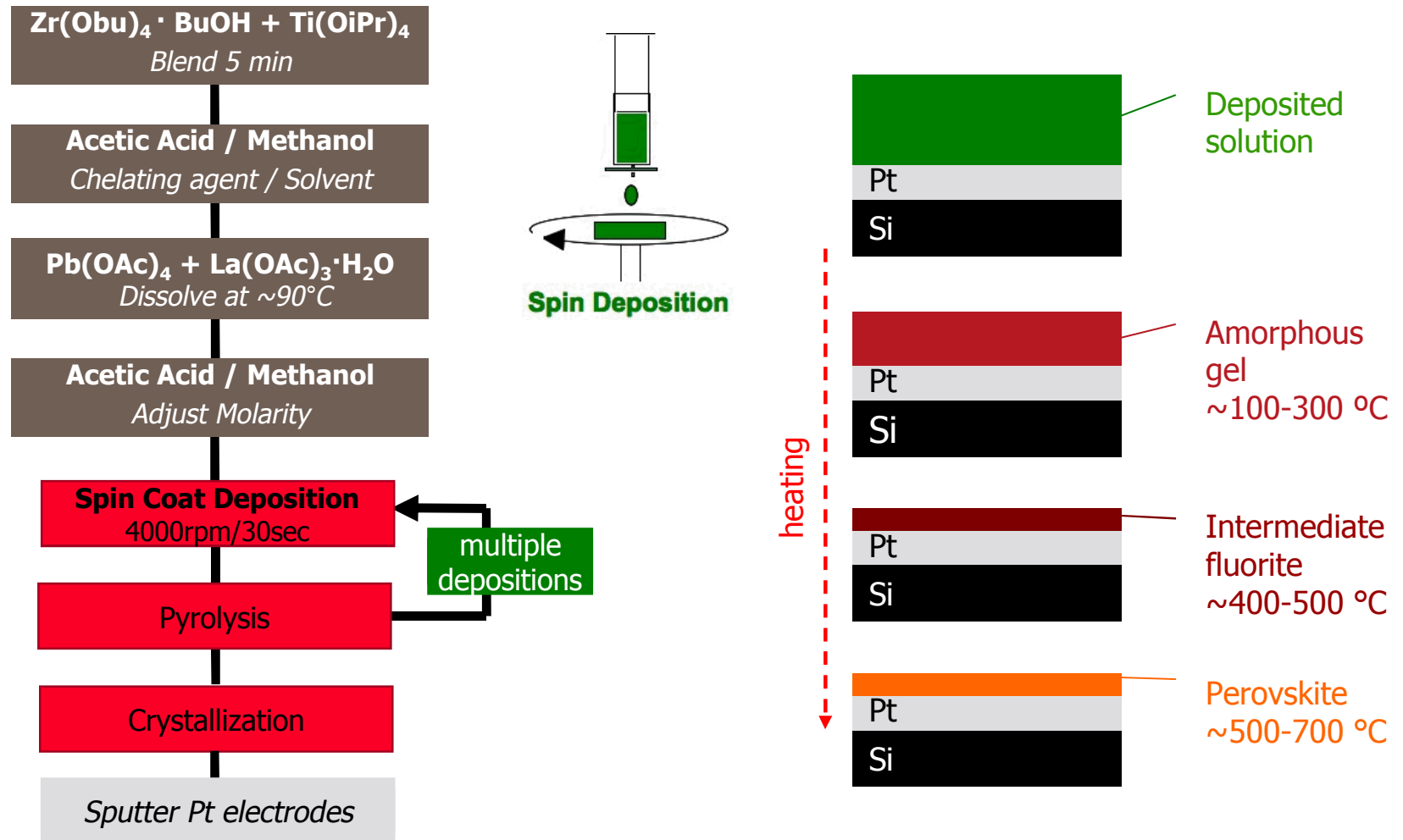


- Titanium 'adhesion' layers by far the most common
 - Adhesion of Pt/ZrO₂ and Pt/TiO₂ not as good as Pt/Ti
- Titanium expands upon oxidation causing hillocks
- Adhesion layer still fails with large temperature swings (>700°)
- **>20 years of research and small improvements made**
- **There must be a better solution!**
 - **ZnO adhesion layers**

Electrode Temperature Stability



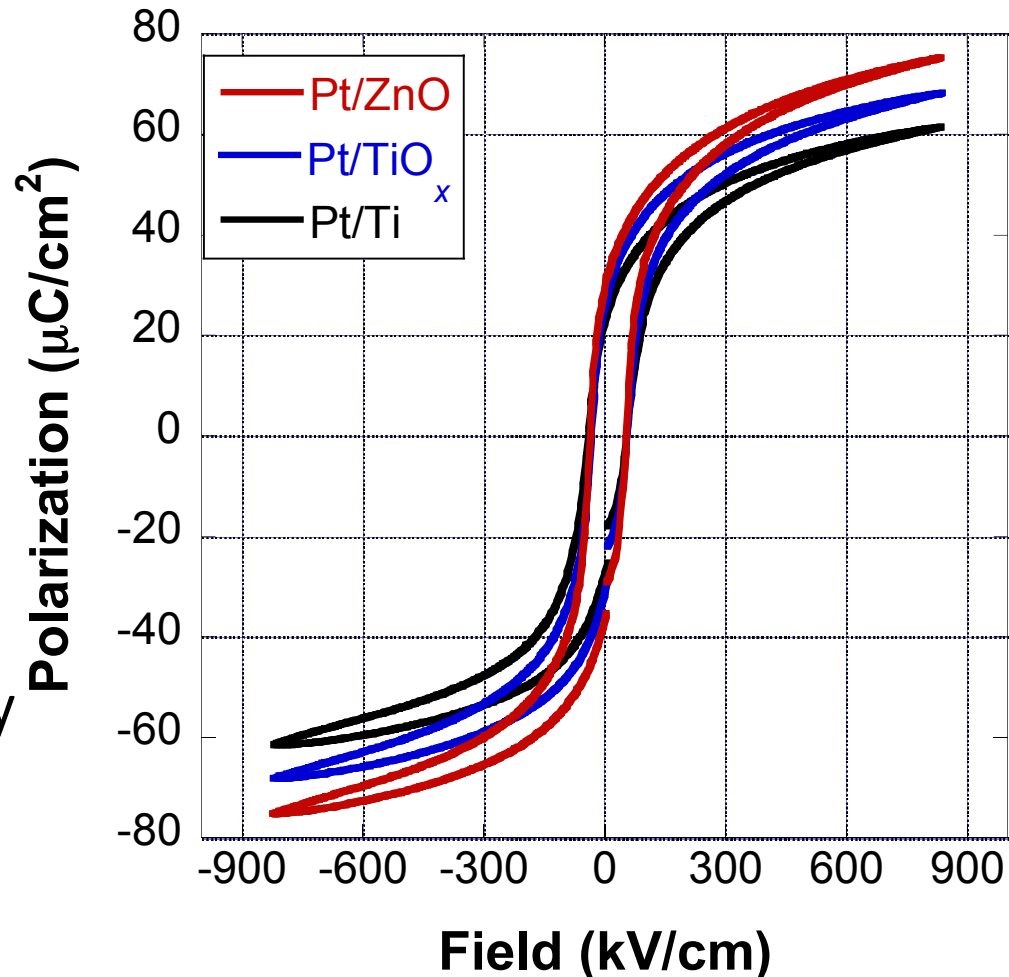
SNL IMO PZT CSD Film Preparation



PZT Films Ferroelectric Properties: Pt/ZnO Substrates Superior

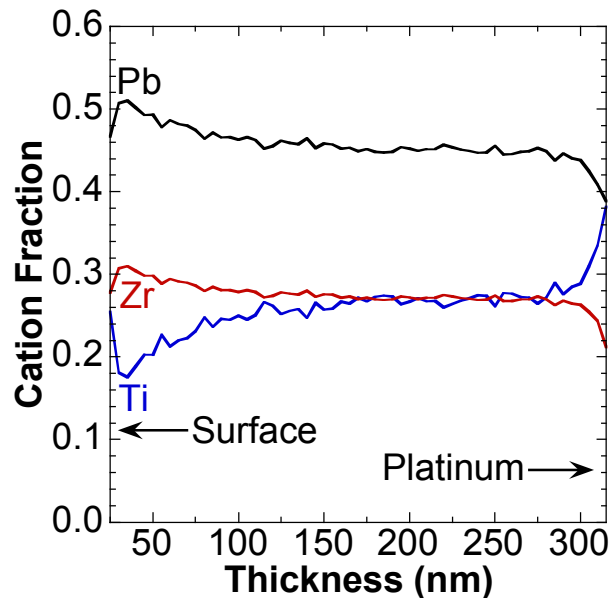
	$P_{\max}$ ($\mu\text{C}/\text{cm}^2$)	P_r ($\mu\text{C}/\text{cm}^2$)	E_c (kV/cm)	K
Pt/Ti	61.5	23.8	47.0	1440
Pt/TiO _x	68.2	27.0	44.1	1620
Pt/ZnO	75.3	32.2	43.8	1740

- Both P_r and K increase on ZnO-buffered substrates
- Coercive field decreases slightly for PZT on ZnO-buffered substrates

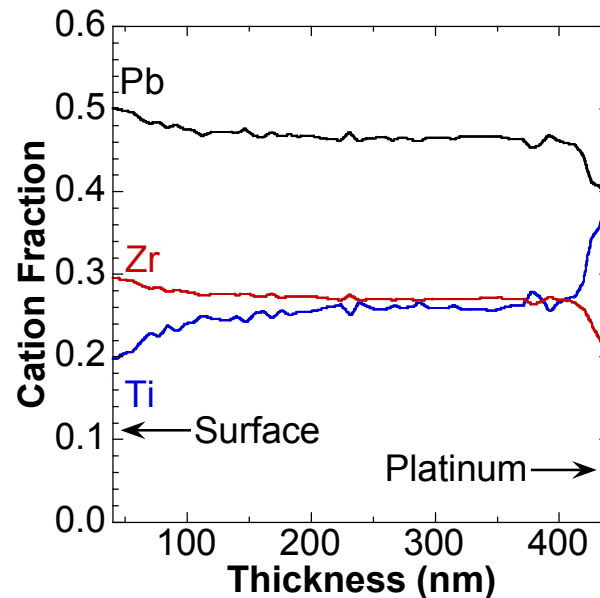


PZT Composition Analysis: No Composition Gradient on Pt/ZnO

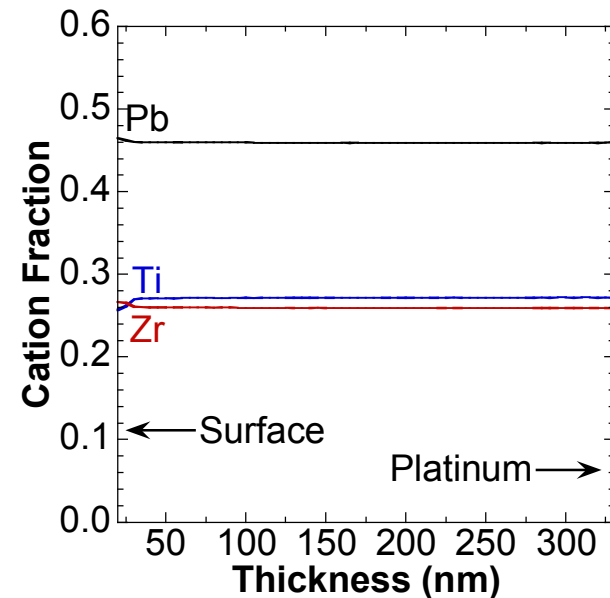
Pt/Ti



Pt/TiO_x

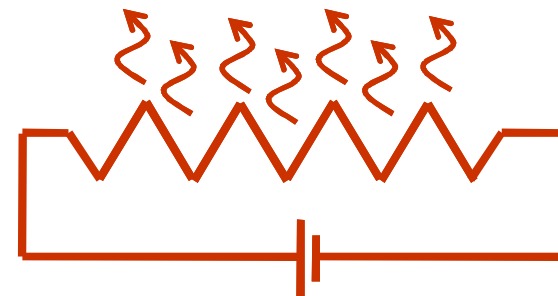
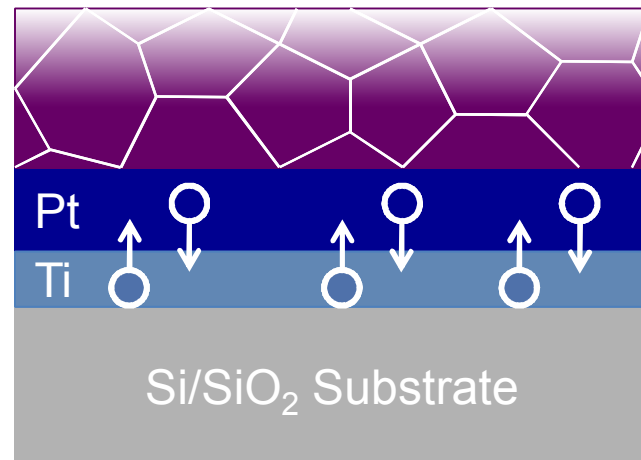
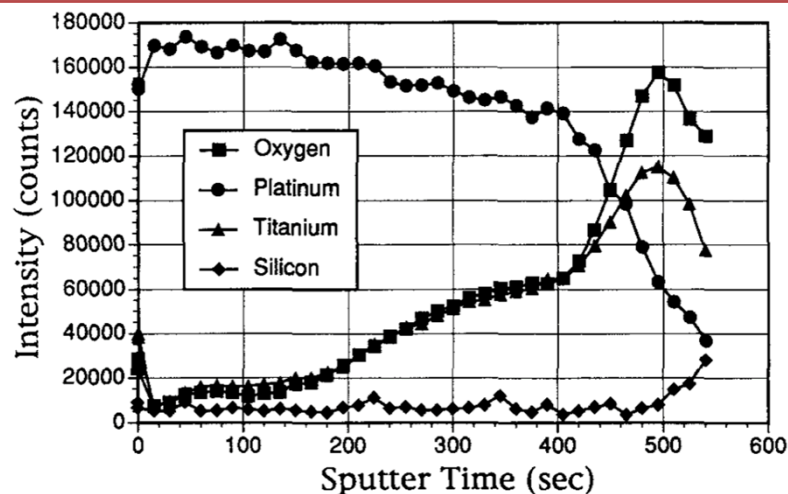


Pt/ZnO

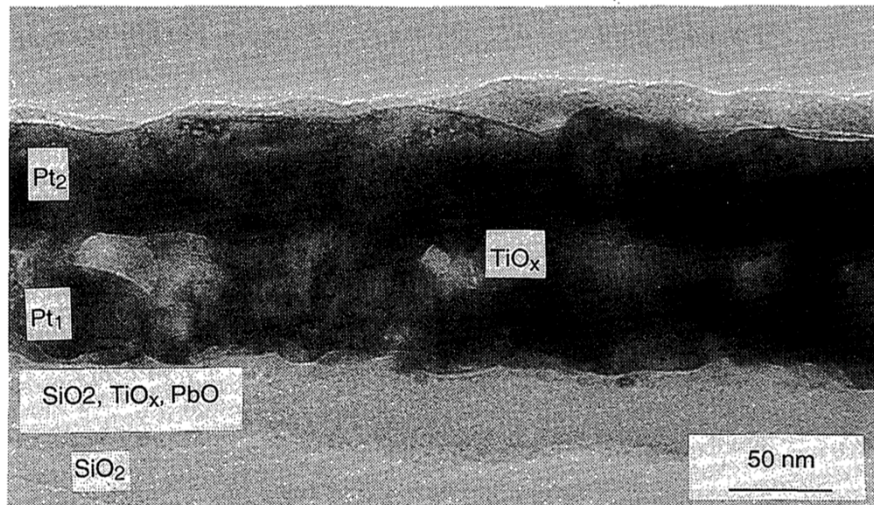


***Substantially improved chemical
homogeneity in films on Pt/ZnO substrates***

Revising prior art: Ti diffuses into Pt!



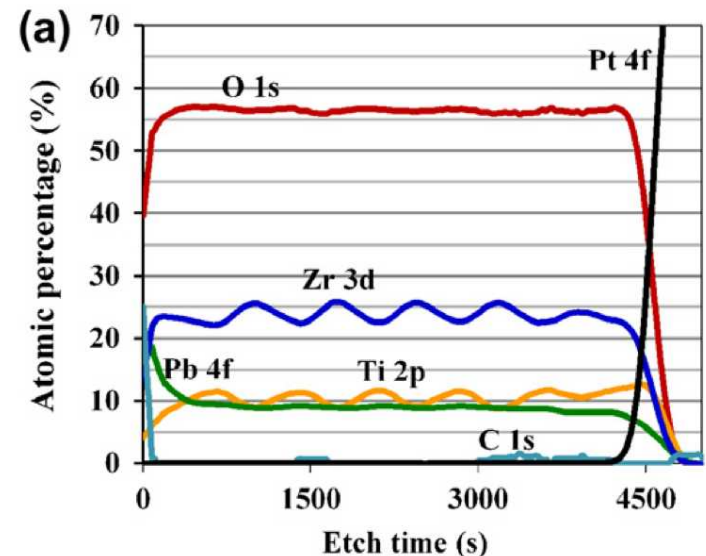
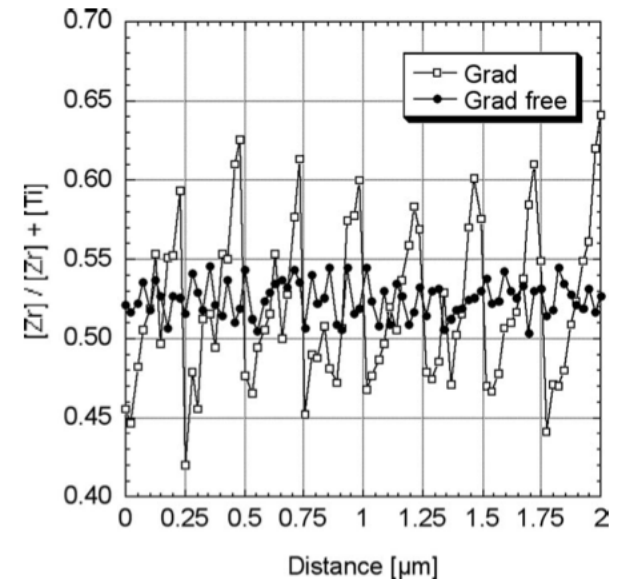
Ti diffusing through Pt can incorporate into the PZT Film



Solution Chemistry Effects?

Open Issues:

- This model cannot explain 'saw-tooth' profiles observed by other groups*
- What roles do solution chemistry and processing conditions play in gradient formation?
- More experiments necessary to isolate controlling variables
 - **Substrate: Pt/Ti vs Pt/ZnO**
 - **Chemistry: IMO vs 2-MOE[‡]**
 - **Pyrolysis: 300, 350, 400° C**
 - Heating Method/Rate: 15, 50, 200° C/s



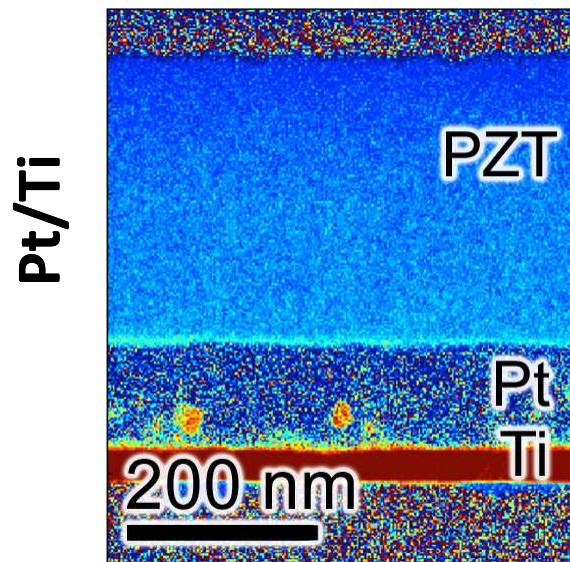
*Amanuma, et al., *Appl. Phys. Lett.* **65**, 3140 (1994)

Calame and Muralt, *Appl. Phys. Lett.* **90**, 062907 (2007), Bastani and Bassiri-Gharb, *Acta. Mater.* **60**, 1346 (2012)

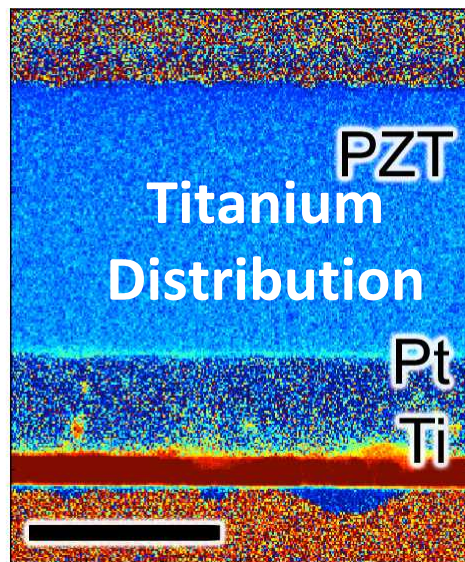
[‡]Based upon: C.D.E. Lakeman and D.A. Payne, *JACerS*, **75(11)**, 3091 (1992)

Solution Chemistry Effect: IMO films

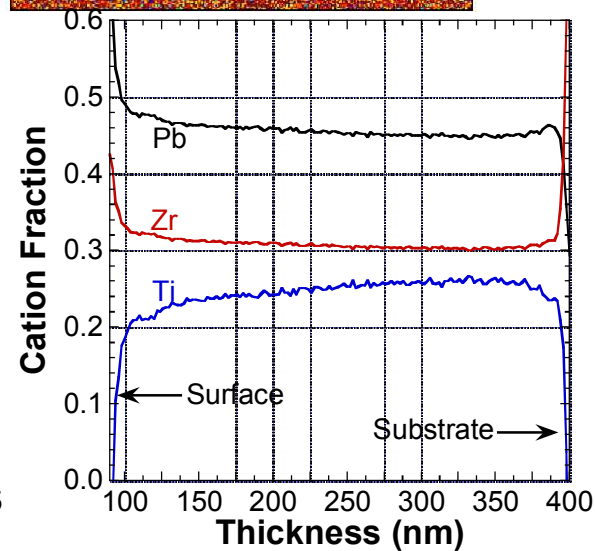
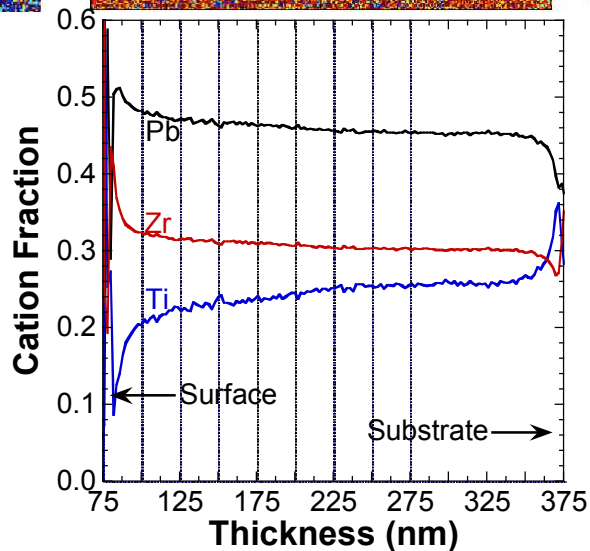
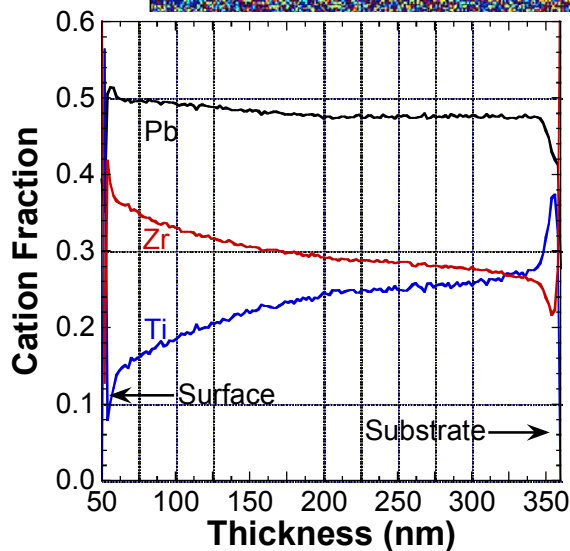
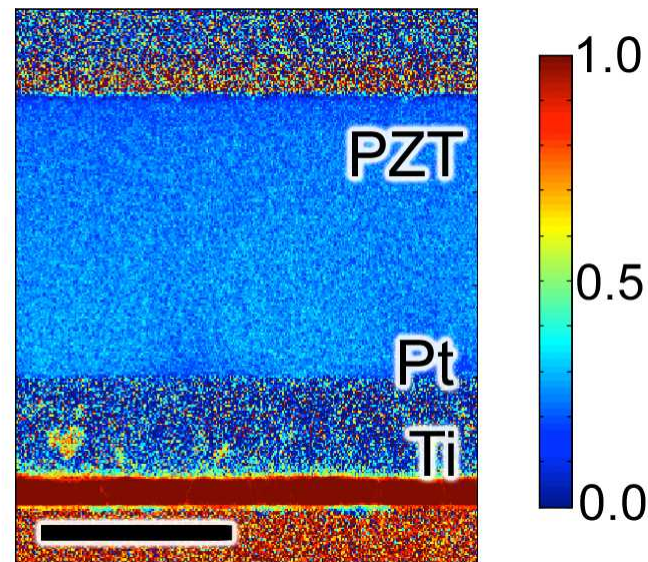
300°C



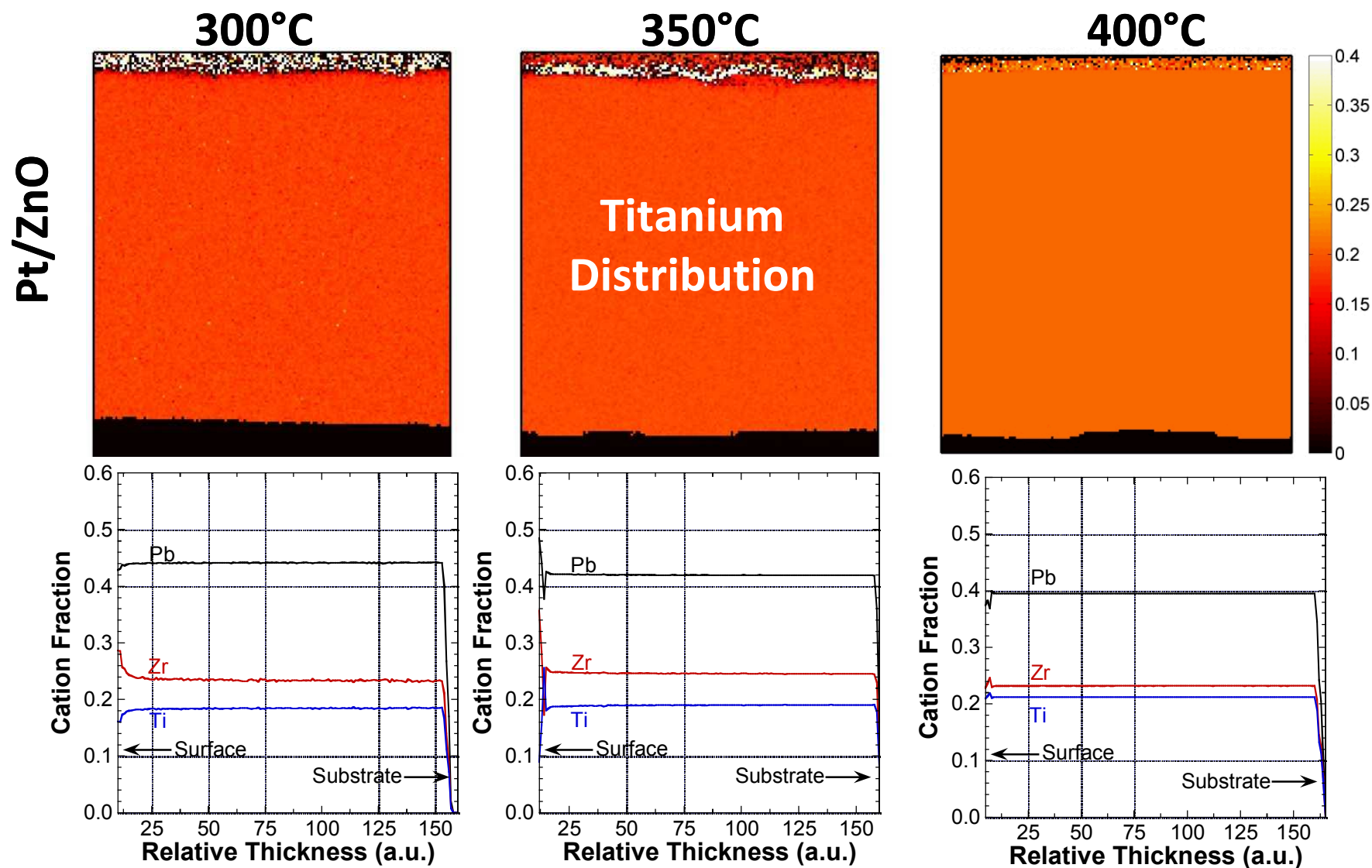
350°C



400°C



Solution Chemistry Effect: IMO Films

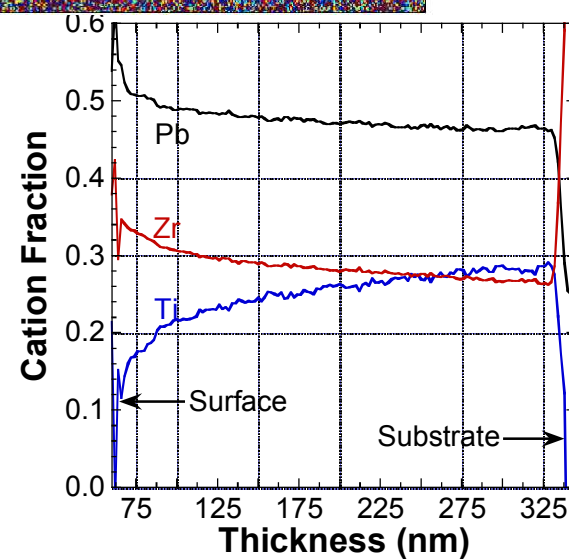
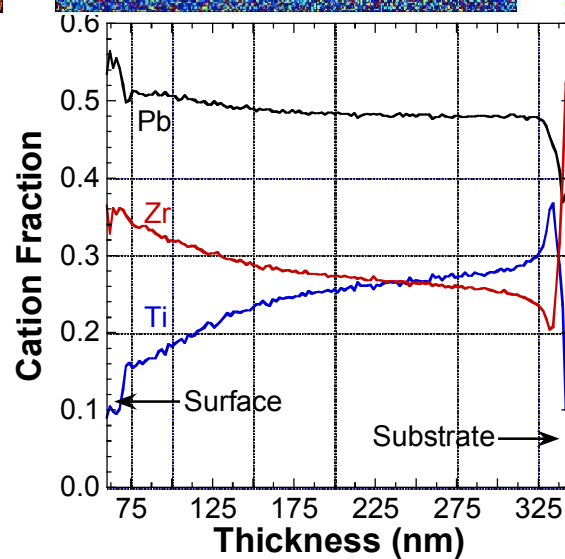
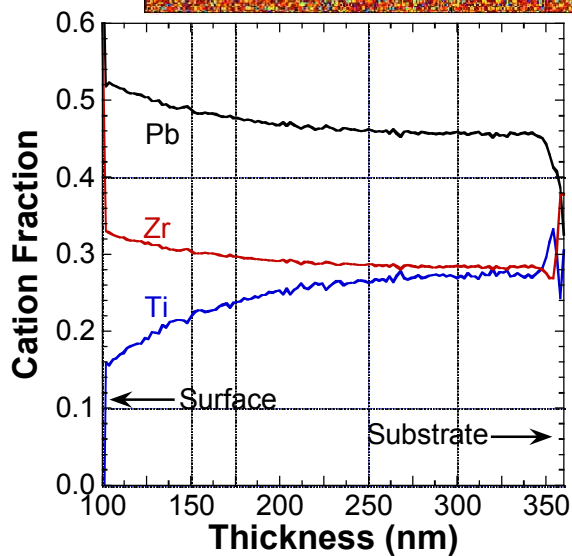
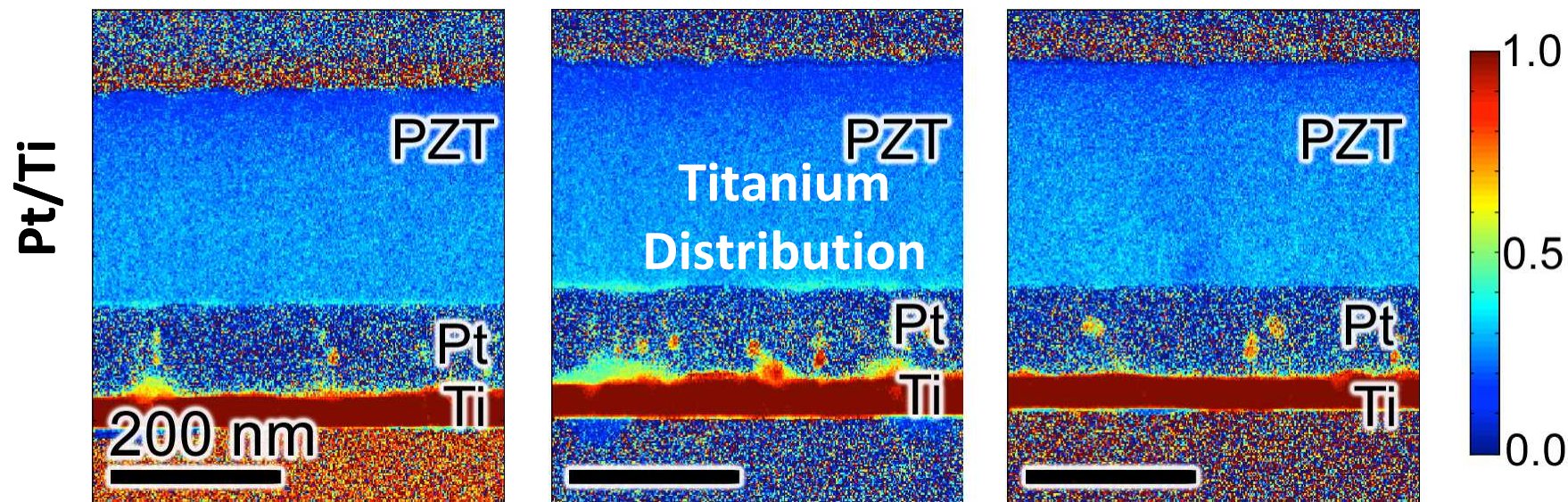


Solution Chemistry Effect: 2-MOE films

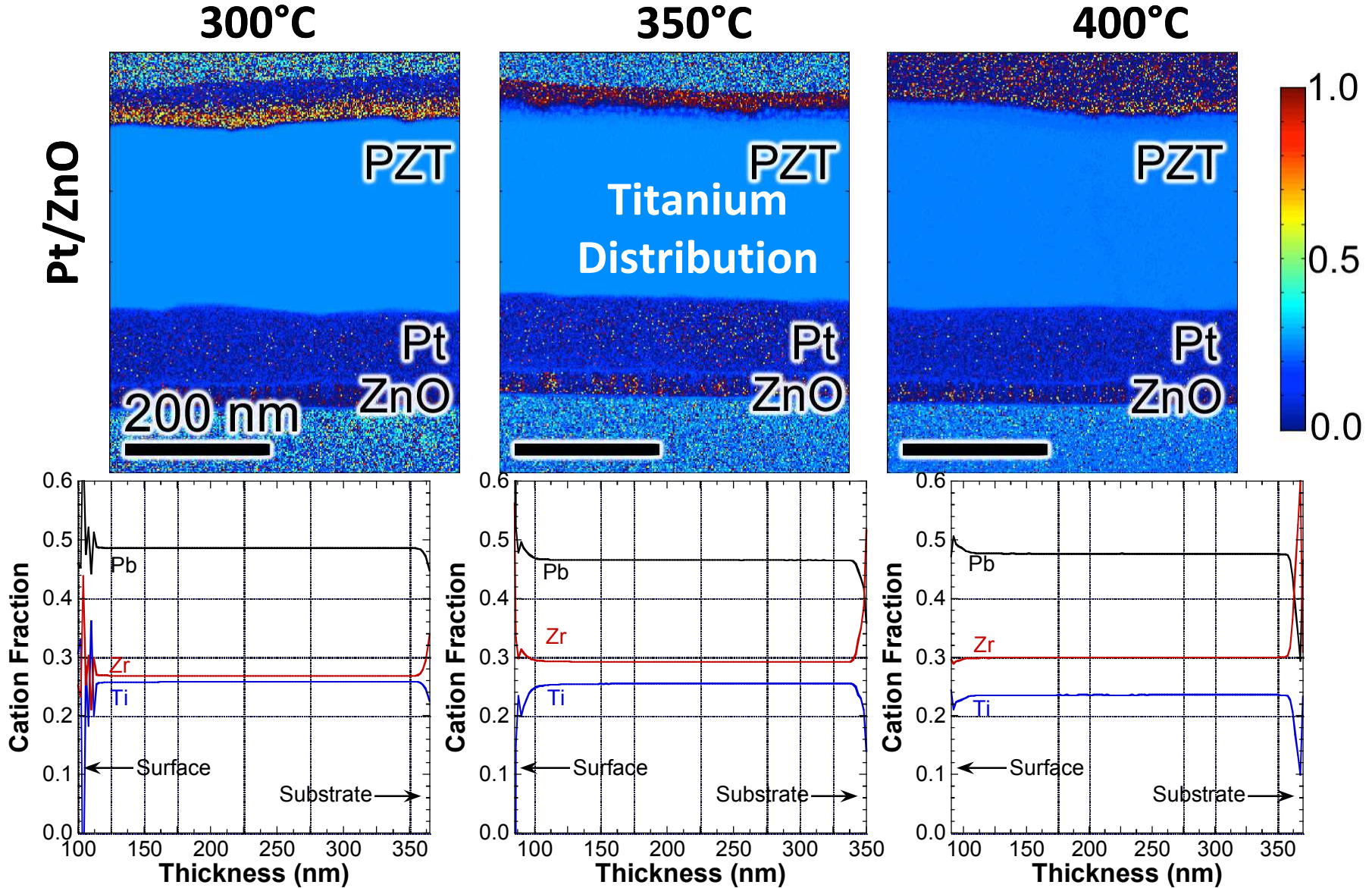
300°C

350°C

400°C



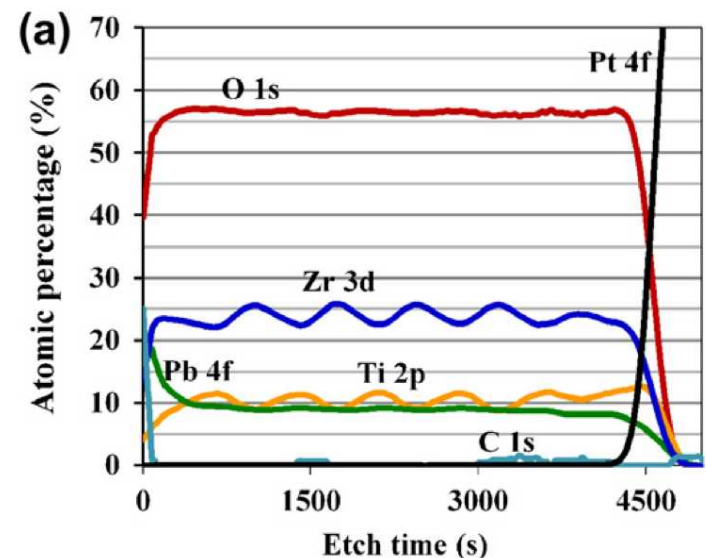
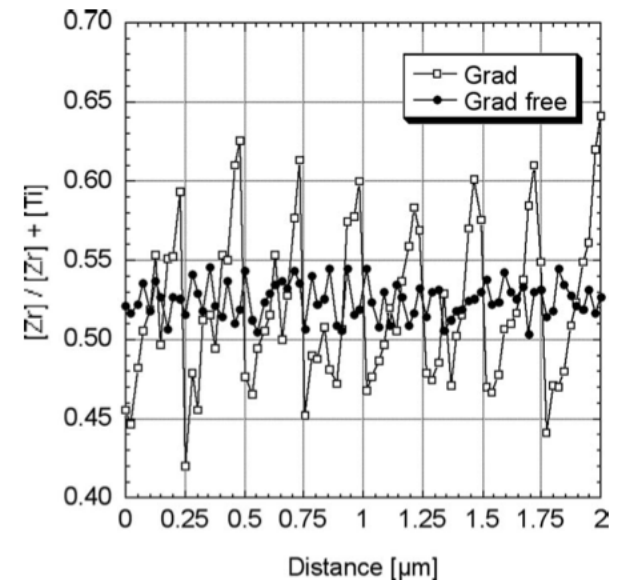
Solution Chemistry Effect: 2-MOE films



Solution Chemistry Effects?

Open Issues:

- This model cannot explain 'saw-tooth' profiles observed by other groups*
- What roles do solution chemistry and processing conditions play in gradient formation?
- More experiments necessary to isolate controlling variables
 - ~~Substrate: Pt/Ti vs Pt/ZnO~~
 - ~~Chemistry: IMO vs 2-MOE[‡]~~
 - ~~Pyrolysis: 300, 350, 400° C~~
 - **Heating Method/Rate: 15, 50, 200° C/s via RTA**

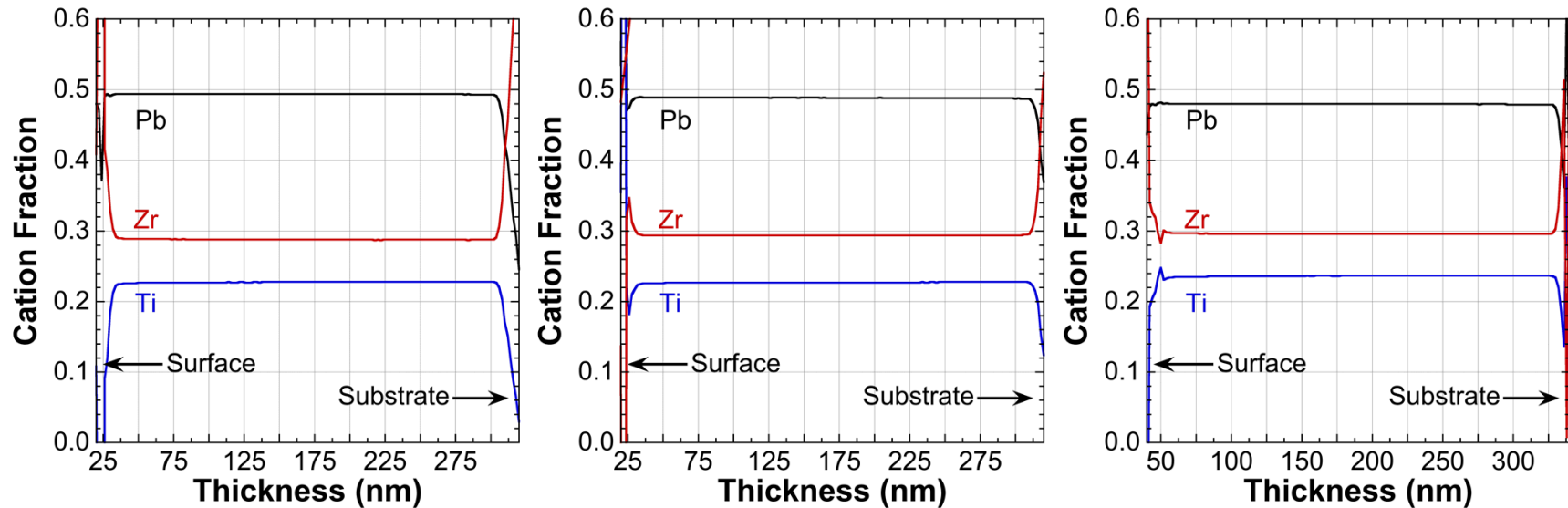
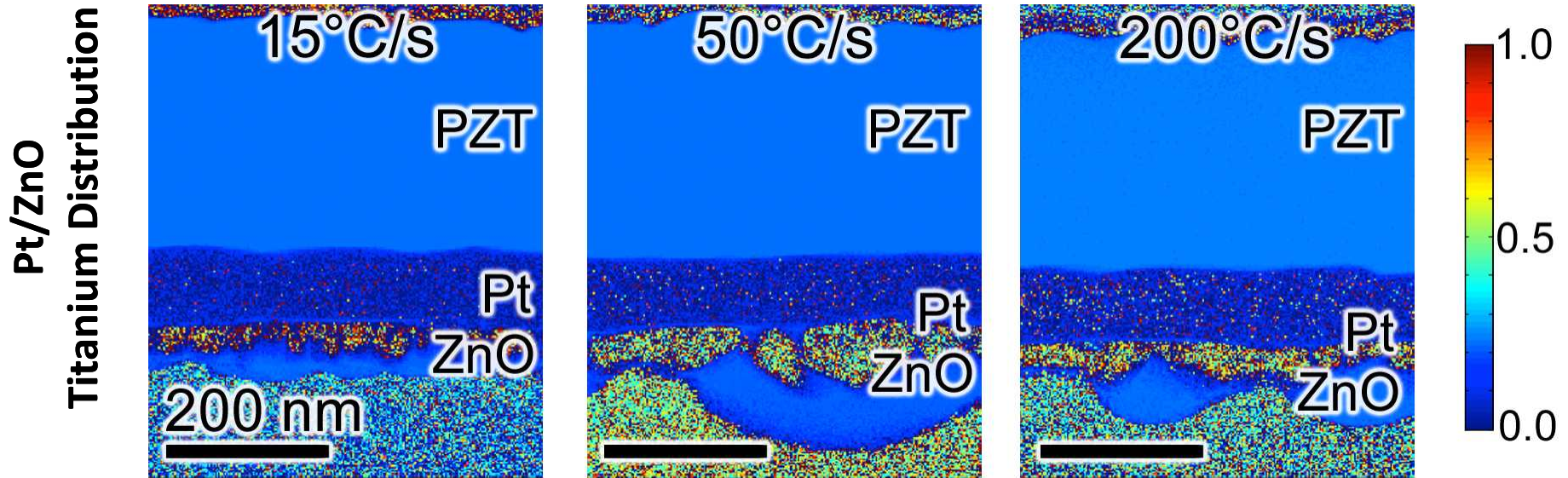


*Amanuma, *et al.*, *Appl. Phys. Lett.* **65**, 3140 (1994)

Calame and Muralt, *Appl. Phys. Lett.* **90**, 062907 (2007), Bastani and Bassiri-Gharb, *Acta. Mater.* **60**, 1346 (2012)

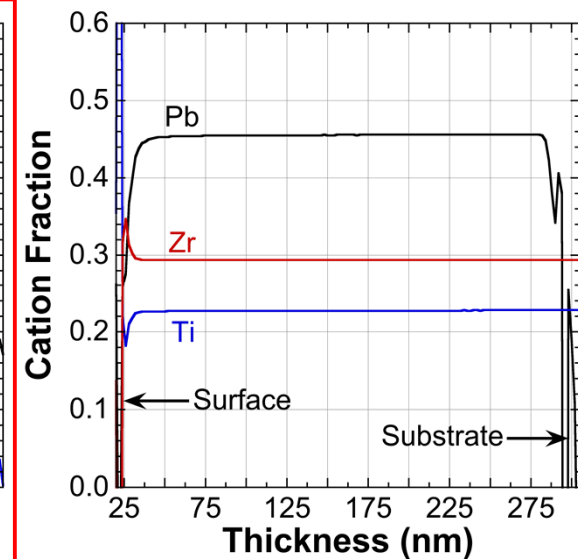
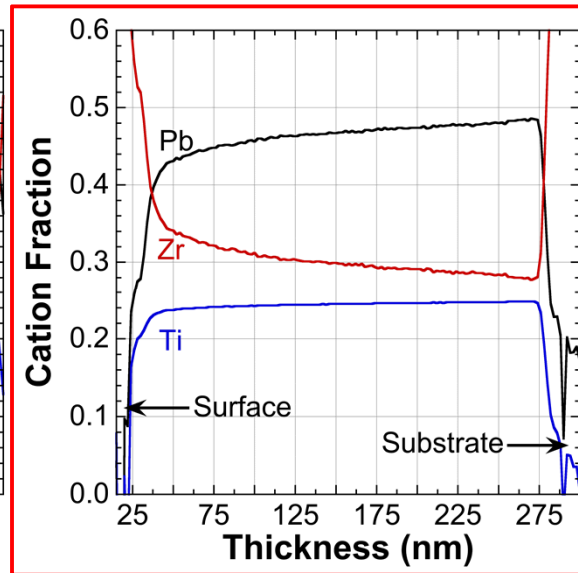
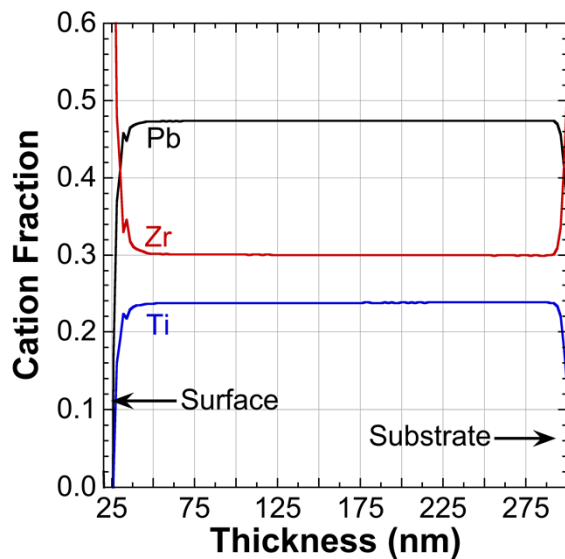
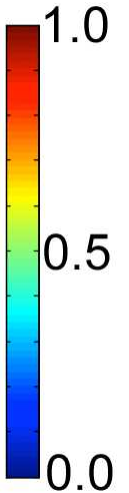
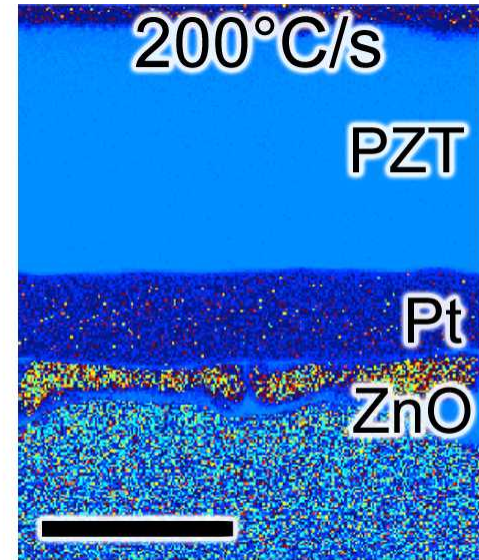
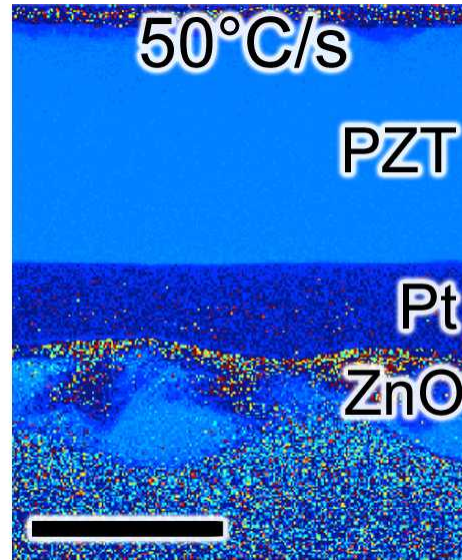
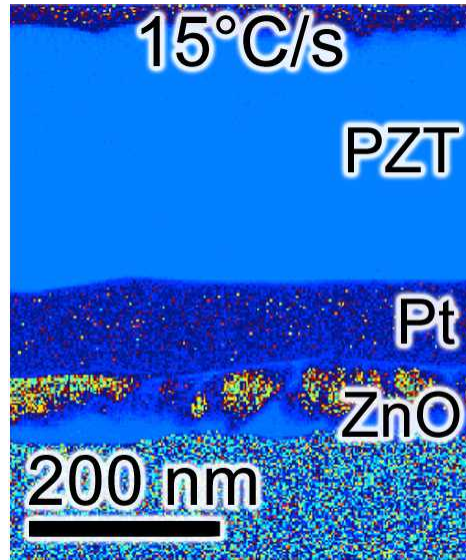
[‡]Based upon: C.D.E. Lakeman and D.A. Payne, *JACerS*, **75(11)**, 3091 (1992)

Ramp Rate Effect: IMO Films

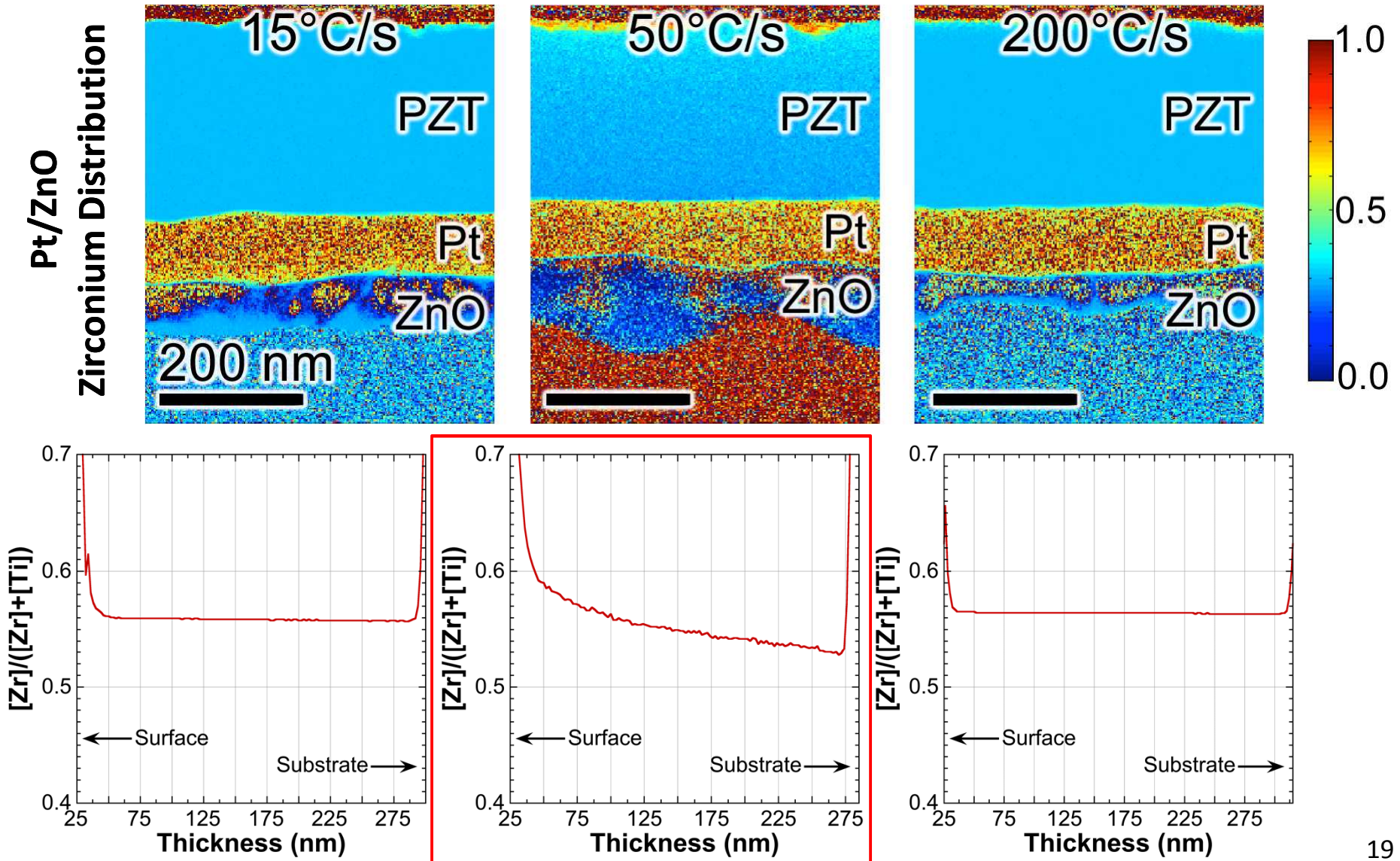


Ramp Rate Effect: 2-MOE Films

Pt/ZnO
Titanium Distribution

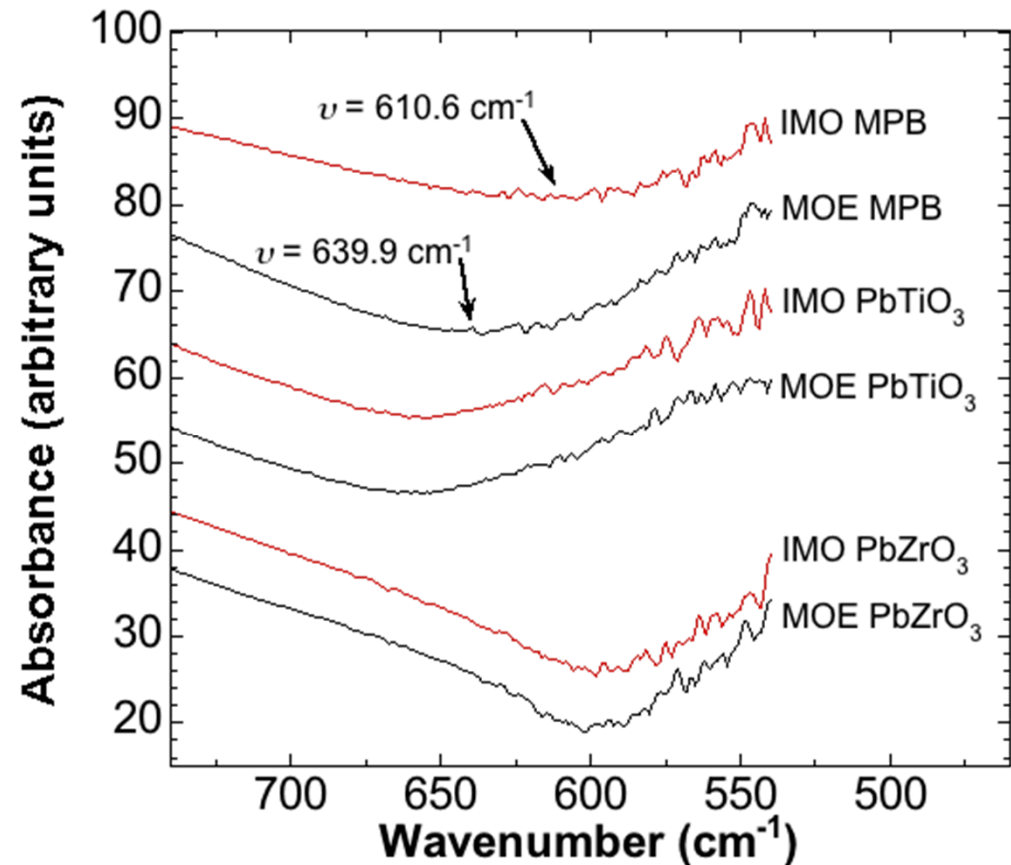


Ramp Rate Effect: 2-MOE Films



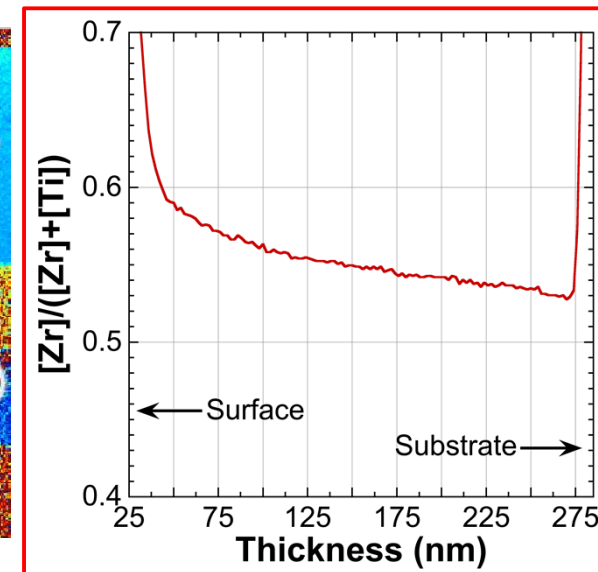
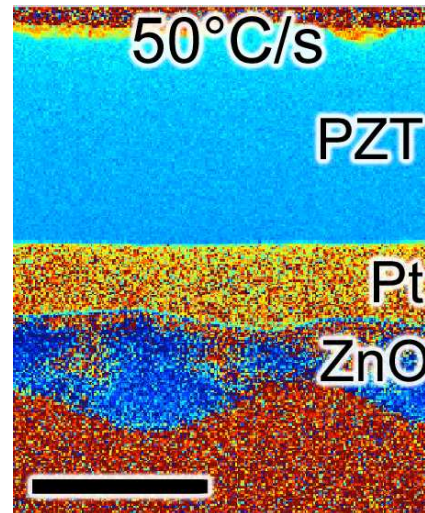
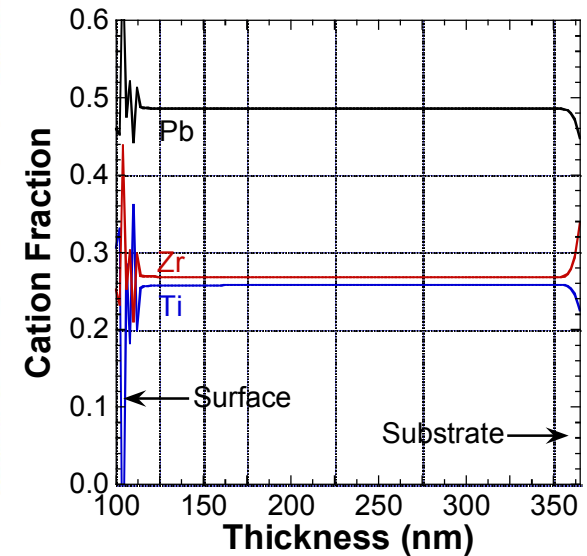
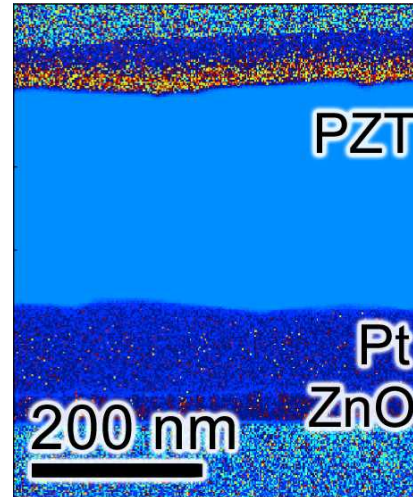
Possible Explanation: IR properties

- Heating mechanism differs
 - RTA=Optical absorption
 - Furnace=optical+conductive
- IR spectra of pyrolyzed gels differs for IMO and 2-MOE chemistries
 - 2-MOE “looks” like PbTiO_3
 - IMO “looks” like PbZrO_3
- PbTiO_3 absorption closer to IR irradiance peak from RTA
 - Potential preferential absorption



Processing of PZT Film: Lessons Learned To Date

- Pyrolysis temperature does not significantly effect gradient formation
- For furnace anneals gradient formation appears to be hindered – even for 2MOE sol-gel chemistries
- Heating rate, method, and solution chemistry does appear to matter*
 - Slight gradient observed in RTA samples with 50° C/s ramp rate



Summary

- IMO PZT films prepared on Pt/ZnO substrates possess improved electronic properties compared to traditional substrates
- ZnO as an adhesion layer enables chemically homogeneous films for most processing conditions
- Titanium/TiO_x may be poor choices for Pt adhesion layers for the high performance device development
- *If a chemically homogeneous film is required, then furnace anneals are preferable*